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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q62494

Ryo KUBOTO, et al.

Appln. No.: 09/817,233

Group Art Unit: 2823

Confirmation No.: 8072

Examiner: Hsien Ming LEE

Filed: March 27, 2001

For: MANUFACTURING METHOD OF SEMICONDUCTOR DEVICE HAVING DRAM

CAPACITORS

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §§ 1.97 and 1.98

Commissioner for Patents Washington, D.C. 20231

Sir:

In accordance with the duty of disclosure under 37 C.F.R. § 1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached PTO/SB/08 A & B (modified) form and/or listed herein and which the Examiner may deem material to patentability of the claims of the above-identified application.

- 1. Japanese Unexamined Patent Publication No. 11-186524, published July 9, 1997. (This reference was previously submitted to the U.S. Patent and Trademark Office with an Information Disclosure Statement dated December 4, 2002. Therefore, a copy is not enclosed herewith.)
- 2. Korean Unexamined Patent Application Publication No. 2000-8804, published February 15, 2000.

One copy of each of the listed documents is submitted herewith.

The present Information Disclosure Statement is being filed after the later of three months from the application's filing date and the mailing date of the first Office Action on the

KUBOTO et al.

Appln. No. 09/817,233

Information Disclosure Statement

merits, but before a Final Office Action, Notice of Allowance, or an action that otherwise closes

prosecution in the application (whichever is earlier), and therefore Applicant is filing

concurrently herewith a Statement Under 37 C.F.R. § 1.97(e). No fee under 37 C.F.R. § 1.17(p)

is required.

In compliance with the concise explanation requirement under 37 C.F.R. § 1.98(a)(3) for

foreign language documents, Applicant encloses herewith a copy of a Korean Office Action

dated January 30, 2003 with a Japanese translation thereof. Also enclosed is an English

translation of the pertinent portions of the Japanese translation which cites such documents and

indicates the degree of relevance found by the foreign patent office.

The submission of the listed documents is not intended as an admission that any such

document constitutes prior art against the claims of the present application. Applicant does not

waive any right to take any action that would be appropriate to antedate or otherwise remove any

listed document as a competent reference against the claims of the present application.

Respectfully submitted,

Registration No. 24,625

J. Frank Osha

SUGHRUE MION, PLLC

Telephone: (202) 293-7060

Facsimile: (202) 293-7860

WASHINGTON OFFICE

PATENT TRADEMARK OFFICE

Date:

APR 1 5 2003

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Ref. Q62494

All of the claims of the invention of the present application are related to an invention of a manufacturing method of a system on-chip semiconductor device mainly characterized by removing the polysilicon film and HSG on the upper surface of the interlayer film, and by maintaining the polysilicon film and HSG on the inner walls of the cylinder. However, described in the Abstract, Embodiment 1, and Figures 1 through 13 of Japanese Unexamined Patent Application Publication H11-186524 (disclosed on July 9, 1997), as well as the Abstract, Embodiment 1, Claim 1, and Figures 1a through 1e of Korean Unexamined Patent Application Publication 2000-8804 (disclosed on February 15, 2000) is the fact that the polysilicon film and HSG on the upper surface of the interlayer insulating film are removed, and the polysilicon film and HSG on the inner walls of the cylinder are maintained. The invention of the present application could be easily invented based on the well-known technology of Japanese Unexamined Patent Application Publication H11-186524 (disclosed on July 9, 1997) and Korean Unexamined Patent Application Publication 2000-8804 (disclosed on February 15, 2000).

(Attachments)

Attachment 1 Japanese Unexamined Patent Application Publication H11-186524 (disclosed on July 9, 1997)

Attachment 2 Korean Unexamined Patent Application Publication 2000-8804 (disclosed on February 15, 2000)

Substitute for Form 1449 A & B/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet	1	of	1

Complete if Known				
Application Number	09/817,233			
Confirmation Number	8072			
Filing Date	March 27, 2001			
First Named Inventor	Ryo KUBOTO			
Art Unit	2823			
Examiner Name	Hsien Ming LEE			
Attorney Docket Number	O62494			

			U.S. I	PATENT DOCUME	ENTS	
Examiner Cite	Document	Number	Publication Date			
Initials*	No.1	Number	Kind Code ² (if known)	MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	
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FOREIGN PATENT DOCUMENTS							
	Cite	Foreign Patent Document			Publication Date	Name of Patentee or	
	No.1	Country Code ³	Number ⁴	Kind Code ⁵ (if known)	MM-DD-YYYY	Applicant of Cited Document	Translation ⁶
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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city, and/or country where published.	Translation ⁶	
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Examiner Signature	Date Considered	

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Applicant's unique citation designation number (optional). ²See Kind Codes of USPTO Patent Documents at www.uspto.gov, MPEP 901.04 or in the comment box of this document. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST. 3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to indicate here if English language Translation is attached.